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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: **Shun-ichi FUKUYAMA et al.**

Group Art Unit: **2813**

Serial No.: **10/630,716**

Examiner: **Stephen W. Smoot**

Filed: **July 31, 2003**

Confirmation No.: **9374**

For: **SEMICONDUCTOR DEVICE USING LOW-K MATERIAL AS
INTERLAYER INSULATING FILM AND ITS MANUFACTURE
METHOD**

Attorney Docket Number: **030860**

Customer Number: **38834**

AMENDMENT UNDER 37 CFR § 1.111

Mail Stop Amendment

Commissioner for Patents

P.O. Box 1450

Alexandria, Virginia 22313-1450

November 15, 2004

Sir:

In response to the Office Action dated August 26, 2004, applicants amend the above-identified application as follows and submits the following remarks.

Amendments to the Claims are reflected in the listing of claims that begins on page 2 of this paper.

Remarks/Arguments begin on page 7 of this paper.